



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: >90%CA
3. SURFACE QUALITY(S1, S2): 60/40(S/D)
4. WAVEFRONT ERROR(RMS): $\lambda/4@633\text{ nm}$ (SUBSTRATE)
5. PARALLELISM(S1, S2): <3 arcmin
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:
 FILTERING(S1): $T_{\text{avg}} > 90\%$, $T_{\text{abs}} > 85\% @ 520-960\text{ nm}, 45^\circ\text{ AOI}$
 $R_{\text{avg}} > 95\%$, $R_{\text{abs}} > 90\% @ 1050-1350\text{ nm}, 45^\circ\text{ AOI}$
 AR COATING(S2): $R_{\text{abs}} < 2\% @ 520-960\text{ nm}, 45^\circ\text{ AOI}$

DRAWING PROJECTION			LBTEK			
	NAME	DATE				
DRAWN	SHAN	OCT./21th/24	SHORTWAVE DICHOIC MIRROR			
APPROVAL	WCHENG	OCT./21th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	0.89g	5:1	A